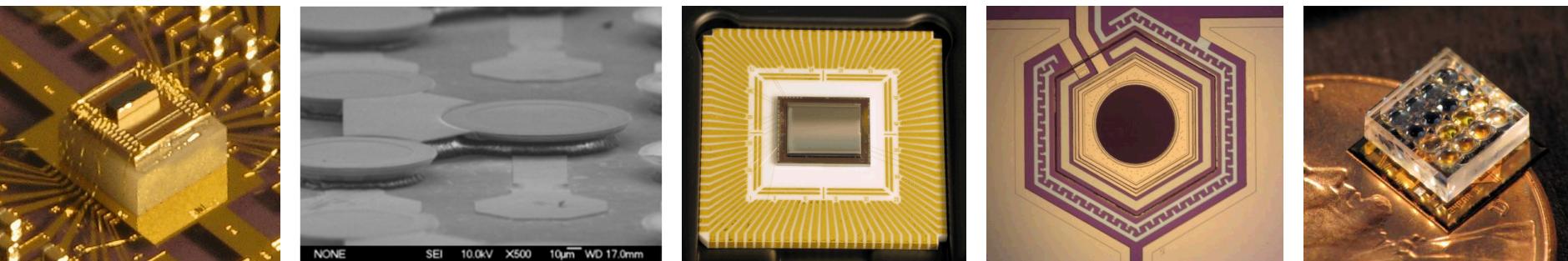


*Exceptional service in the national interest*



## Heterogeneous Integration of III-V Photonics and Silicon Electronics for Advanced Optical Microsystems

Gordon A. Keeler, Kent M. Geib, Darwin K. Serkland, Gregory M. Peake, Mark E. Overberg,  
Jeffrey G. Cederberg, Thomas M. Gurrieri, Jin K. Kim, and Charles T. Sullivan

**Sandia National Laboratories**



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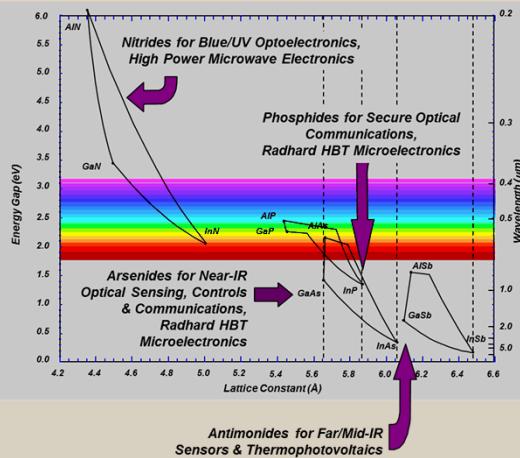
# Heterogeneous Integration of Photonics at Sandia

## microsystems capability

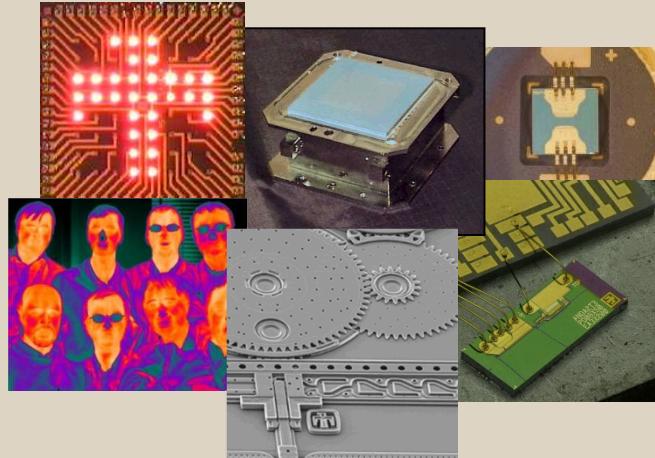


SiFab: 11,900 ft<sup>2</sup> Class 1  
MicroFab: 14,230 ft<sup>2</sup> Class 10/100

## compound semiconductors



## advanced photonics



## Rationale for integration

- SWAP-C: size, weight, and power; cost
- performance: combine technologies, improve interconnect
- diverse functionality: optical, RF, MEMS, analog, chem, bio
- agility & turn time: prototyping and low-volume
- trust: secure microsystems

low volume,  
high value

## Approaches to integration

- in-package
- this talk → die-to-die: flip-chip bonding, micro-optics, etc.
- talk 17.2, next → wafer-level: interconnect bonding (3D DBI)
- wafer-level: epitaxy bonding (dielectric interfaces)
- monolithic integration

common at Sandia

# Outline

## Overview of Si/III-V heterogeneous integration

- rationale and methods

## Selected photonics programs leveraging integration

- imaging sensor development

- nBn detector arrays based on GaSb
- indium-based flip-chip to silicon ROICs

- optical microsensor prototyping

- photonic proximity fuzing
- high-power lasers, detectors, micro-optics

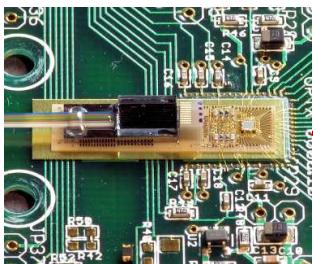
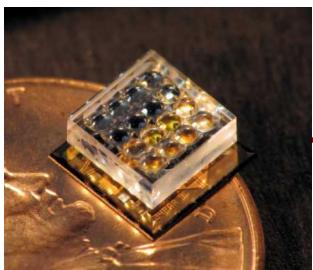
- low-power data communications R&D

- high-performance computing & cryogenic satellite applications
- 32-nm CMOS, dense VCSEL & photodiodes, micro-optics, multi-core fibers

- pathfinder technologies

- microsystem-enabled photovoltaics
- III-V/CMOS microelectronics
- high-performance & extreme environment applications

## Outlook and Summary



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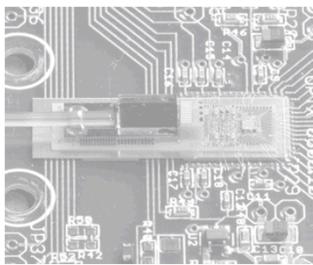
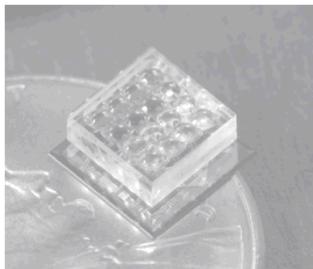
### – low-power data communications R&D

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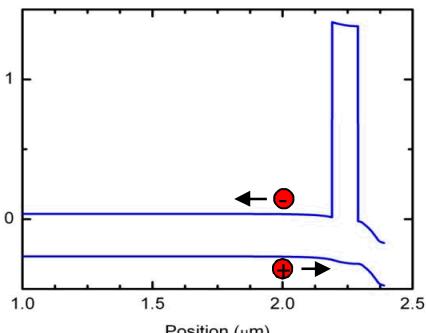
### – pathfinder technologies

- microsystem-enabled photovoltaics
- III-V/CMOS microelectronics
- high-performance & extreme environment applications

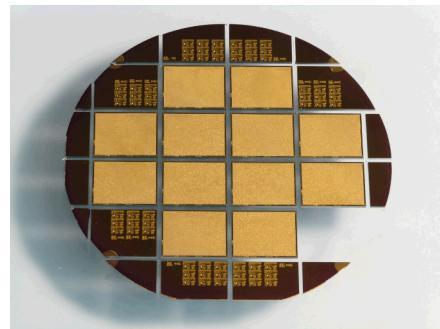
## Outlook and Summary



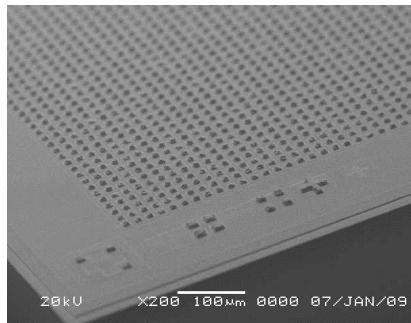
# MWIR/LWIR nBn Focal Plane Arrays



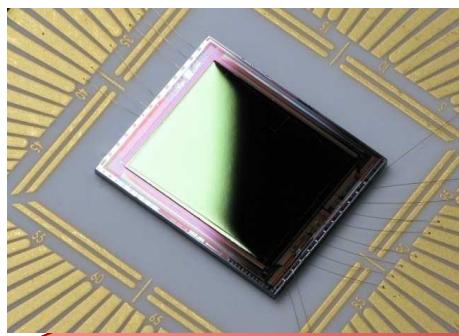
nBn band diagram



GaSb detector epitaxy



nBn array with indium bumps



hybridized nBn FPA prototype

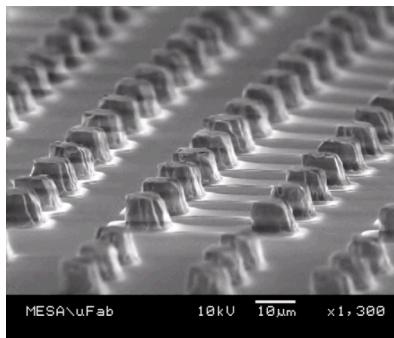
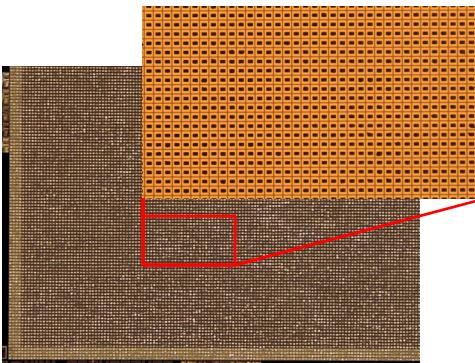


MWIR still frame, 160K

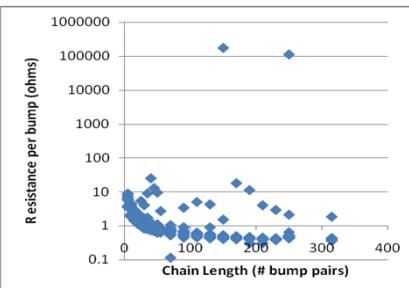
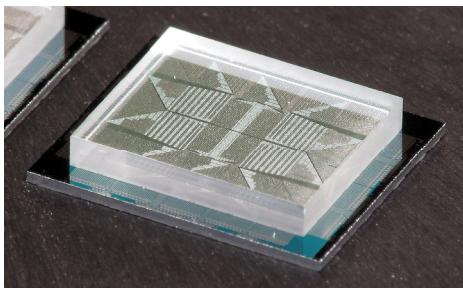
- nBn rapidly approaching MCT sensor performance
- In-house development of nBn detector technology includes growth, fabrication, integration, and device/system testing
- Requires hybridization of large ( $\leq 1\text{MP}$ ) GaSb detectors to CMOS ROICs

# FPA Integration Process Overview 1

- ROIC hybridization after back-end fabrication & detector testing
  - solder dam, underbump metallization
  - indium solder bumps (electroplating or evaporation)
  - singulation
  - flip-chip bonding



pixels with indium bumps (~8μm)



bonded test chips to assess yield (>0.9999)



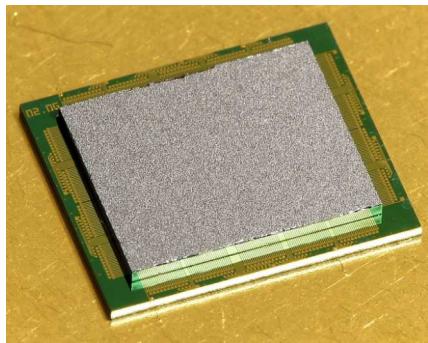
semi-automated flip-chip bonder

## Capabilities:

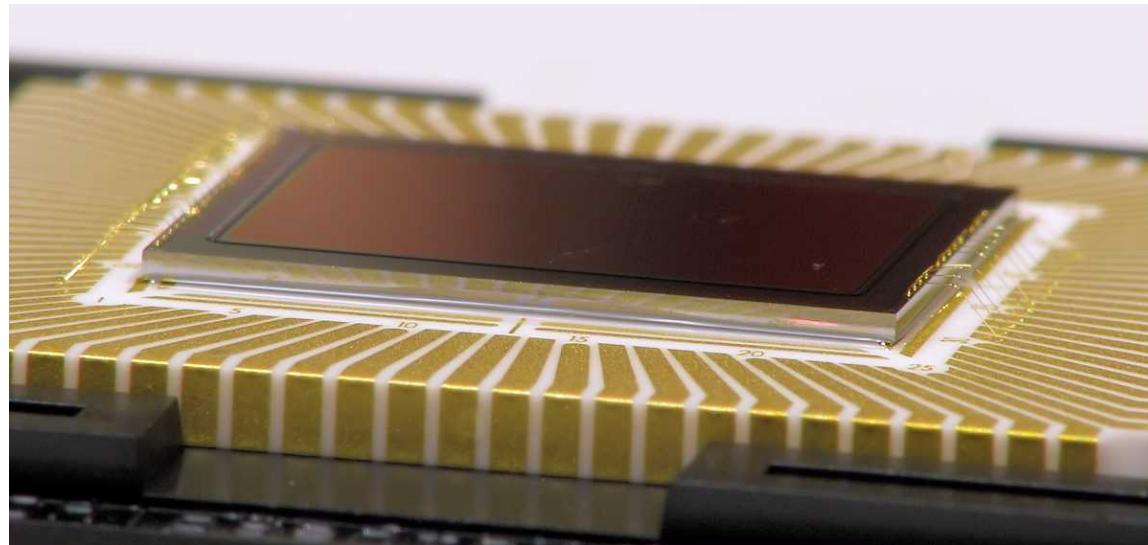
- +/- 1 micron xyz accuracy, excellent planarity
- 400x imaging, alignments at >450C
- thermocompression bonding up to 100 kg
- flip-chip, die attach, UV-curing, fiber alignment, replication
- “dry flux” vapor removes oxides to improve bonds

# FPA Integration Process Overview 2

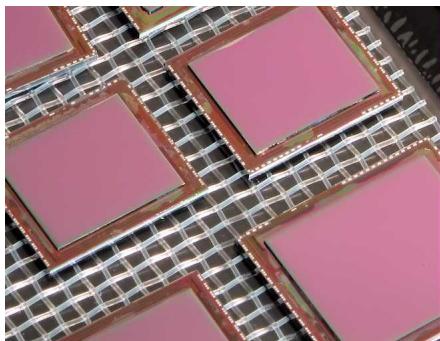
- Post flip-chip processes
  - **epoxy underfill**
  - **backside grinding & polishing**
  - **precision optical coatings**
  - **packaging**
  - **cryo testing**



full thickness hybridized chips



FPA packaged for cryo testing



FPAs after thinning and AR coat



MWIR imaging with nBn sensor

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- high-power lasers, detectors, micro-optics

- low-power data communications R&D

- high-performance computing & cryogenic satellite applications
- 32-nm CMOS, dense VCSEL & photodiodes, micro-optics, multi-core fibers

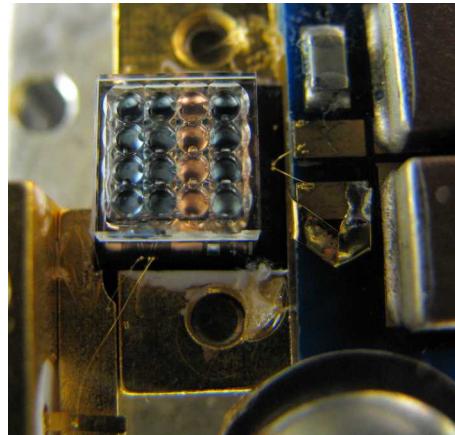
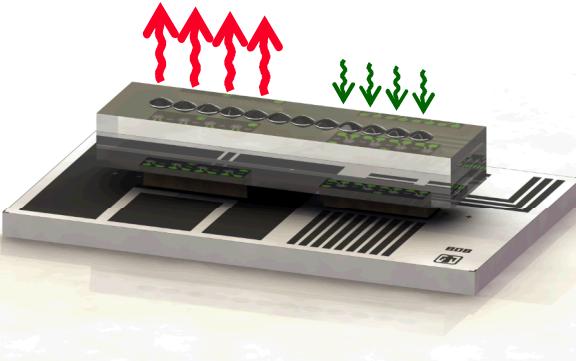
- pathfinder technologies

- microsystem-enabled photovoltaics
- III-V/CMOS microelectronics
- high-performance & extreme environment applications

## Outlook and Summary

# Microscale Optical Sensors

- Robust photonic proximity fuzes employ flip-chip optoelectronics and micro-optics
  - very compact, g-hard; high sensitivity; narrow FOV; immunity to RF jamming
  - requires high-power VCSELs; fast photodiodes at 980nm; micro-optics
  - flip-chip integration of optoelectronics on AlN or diamond heat spreaders



time-of-flight optical range sensor



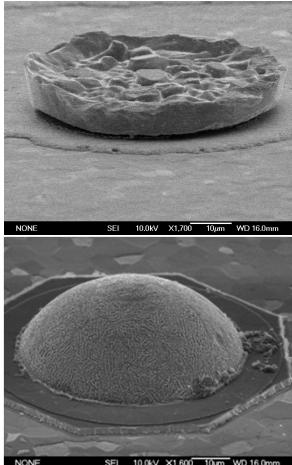
microfuz with support electronics



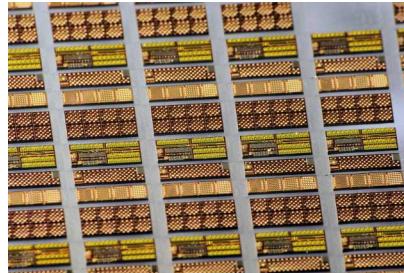
photonic fuzing demo with micro-optics  
and VCSEL transmitter array

# Optical Microsystem Integration

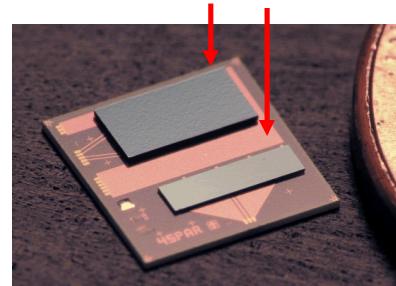
- Processes combined into photonics fabrication
  - solder dam, underbump metallization, solder bump
  - thinning and AR coatings
  - singulation (scribe and break)
  - flip-chip attach
- Micro-optics fab & align
  - diamond turning
  - molding in optical plastics
  - active alignment
  - UV epoxy attach



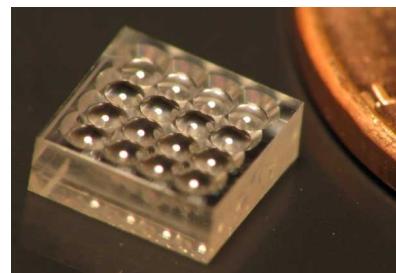
indium solder reflow for thermal transfer



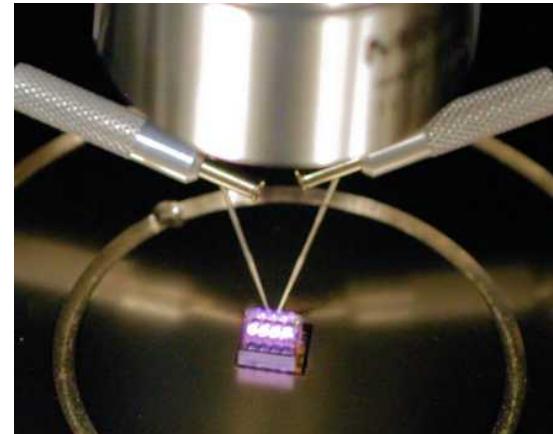
photodiode and VCSEL arrays



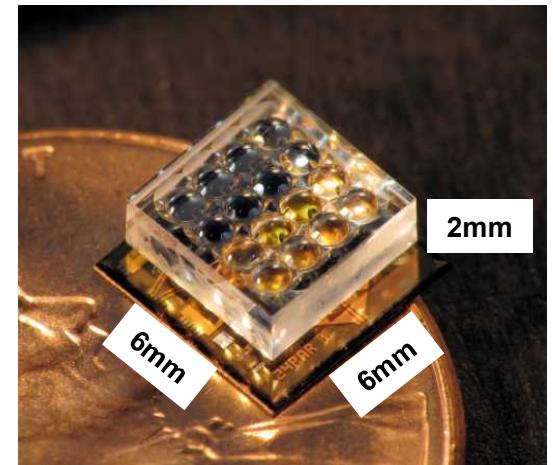
populated fuse submount



microlens array



integrated component testing



high-power optical proximity sensor

# Outline

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- low-power data communications R&D

- high-performance computing & cryogenic satellite applications
- 32-nm CMOS, dense VCSEL & photodiodes, micro-optics, multi-core fibers

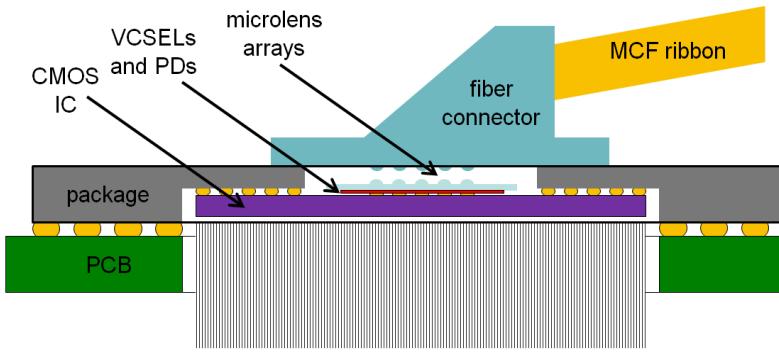
- pathfinder technologies

- microsystem-enabled photovoltaics
- III-V/CMOS microelectronics
- high-performance & extreme environment applications

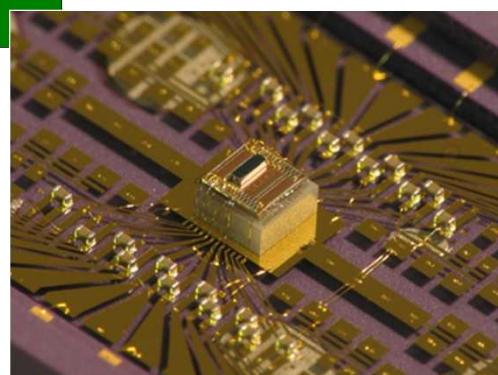
## Outlook and Summary

# Optical Interconnects for High Performance Computing

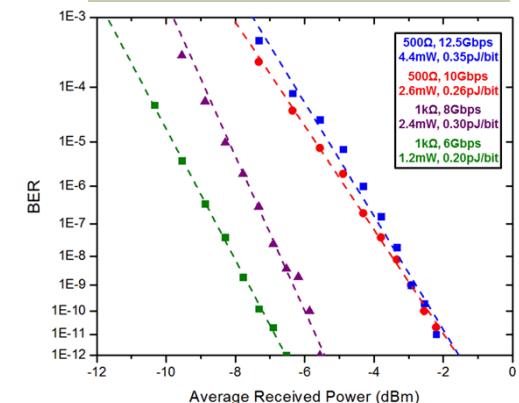
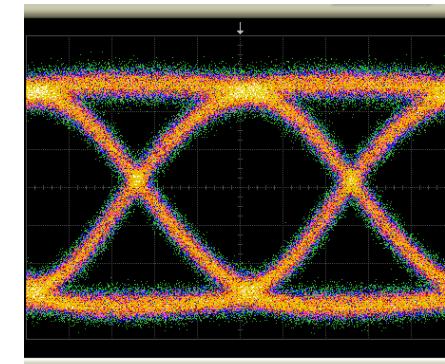
- Dense integration of photonics and CMOS for advanced interconnect technologies
  - hybrid integration for very high density and low electrical parasitics
  - targets  $<1$  pJ/bit and  $>1$  Tbps/mm<sup>2</sup>
- Development of circuits, photonics, optics and integration techniques
  - transmit/receive circuits in 32-nm and 45-nm CMOS (TAPO)
  - combines VCSEL and photodiode arrays, micro-optics, custom fiber



multichannel interconnect concept



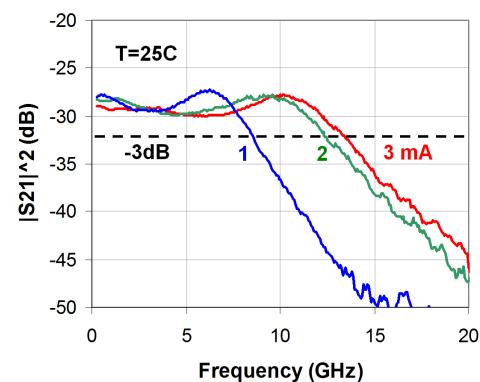
packaged CMOS/VCSEL assembly



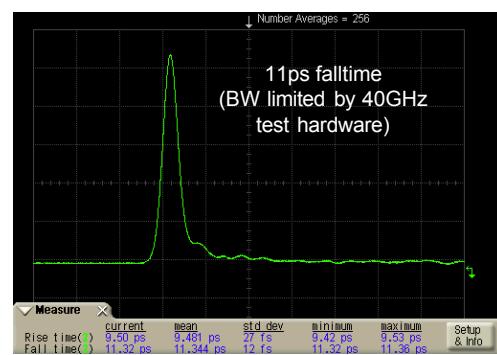
system link testing

# Interconnect Components

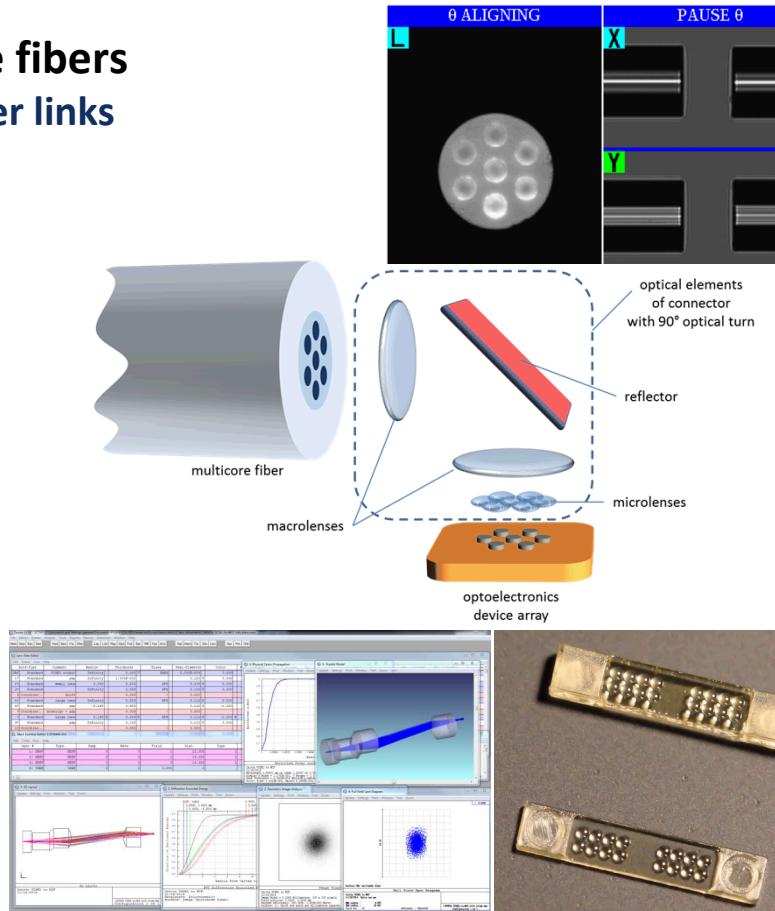
- development of high-density optoelectronics arrays
  - low-power VCSELs designed for high BW at low drive current
  - photodiodes >40Gb/s with very low capacitance through flip-chip integration
- Micro-optics designed for coupling to multicore fibers
  - custom micro-optics developed for multicore fiber links



VCSEL performance



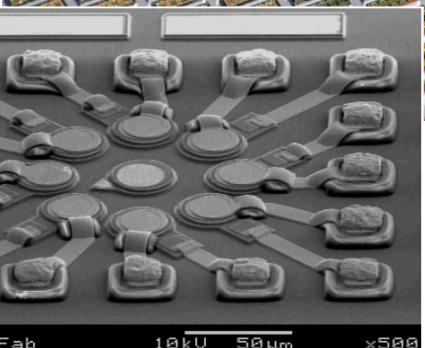
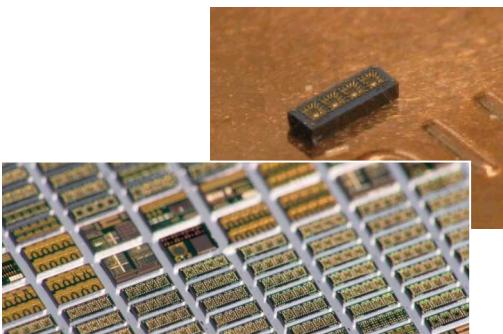
InGaAs photodiode performance



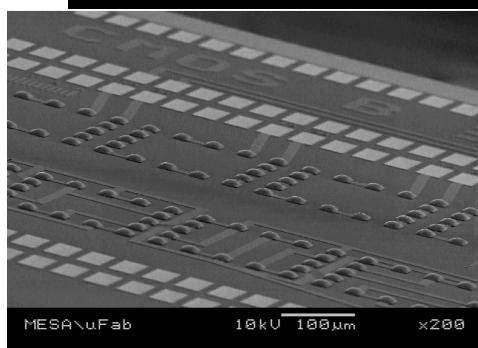
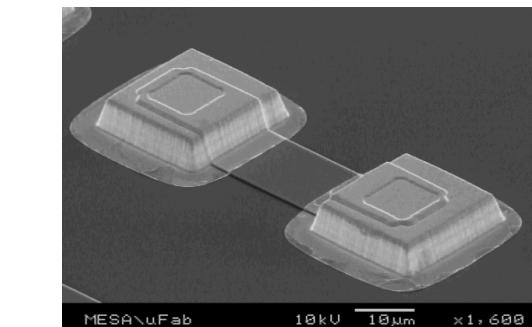
micro-optics and multicore fibers

# Interconnect Heterogeneous Integration

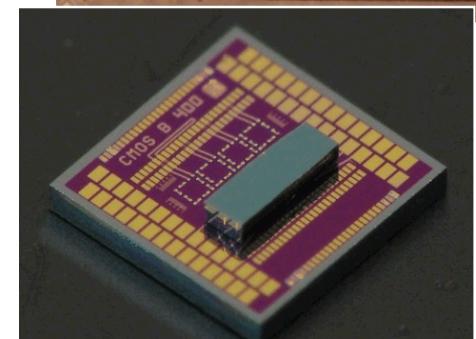
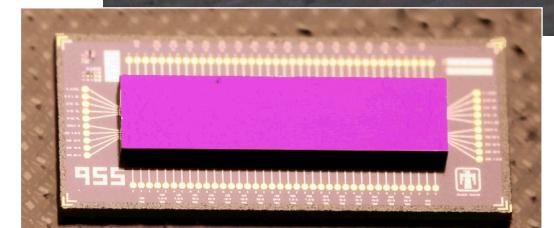
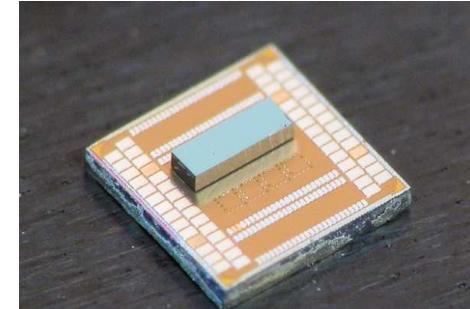
- III-V processes combined into photonics fabrication
  - AuSn bumps, 100 $\mu$ m substrate thinning, AR coating, scribe and break
- CMOS processed in die form
  - plated underbump and bumps
- Flip-chip integration



VCSEL and PD arrays  
on GaAs and InP



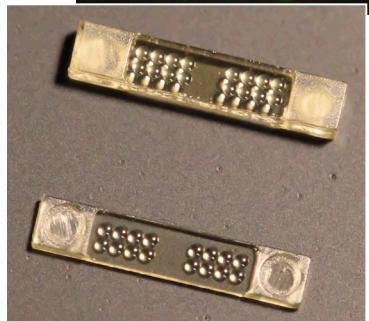
CMOS IC prior to flip-chip  
50 $\mu$ m bump pitch (AuSn, SAC...)



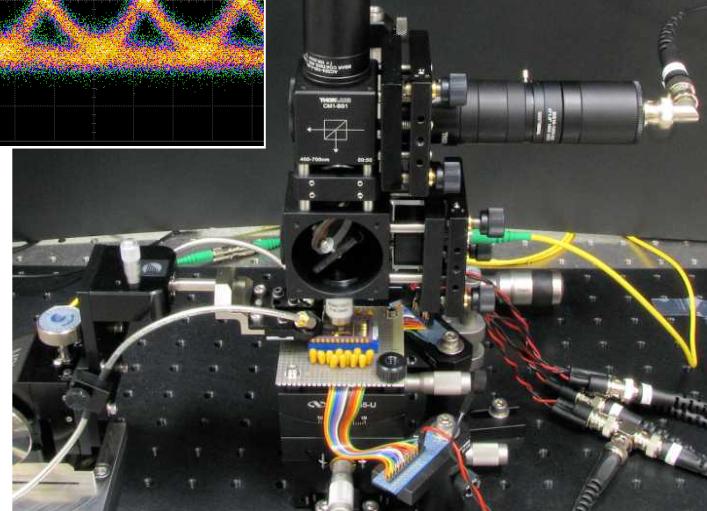
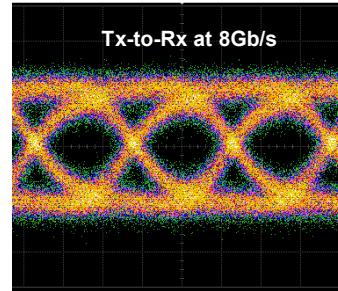
CMOS IC with III-V optoelectronics

# Interconnect Testing

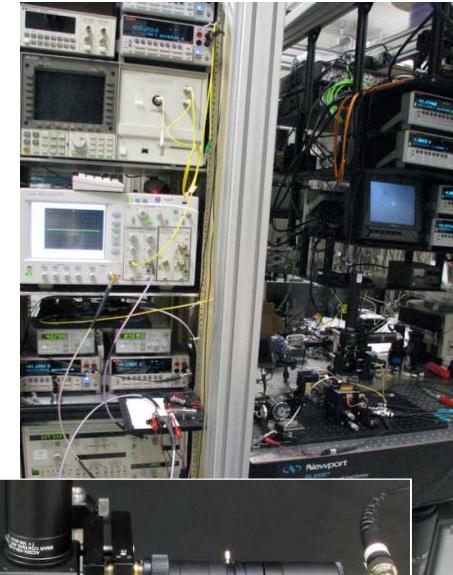
- Hybridized parts packaged for high-speed opto-electronic testing
  - DC wirebonding, RF probing
  - active fiber alignment
- Single channel links demonstrated using 45-nm CMOS
  - 10Gbps at 1.7 pJ/bit
- Ongoing characterization of new link and components
  - test & attach multicore fiber, micro-optics, and 32-nm IC



packaged CMOS/III-V photonics



system link testing



multicore fiber and molded microlens arrays

# Outline

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- rationale and methods

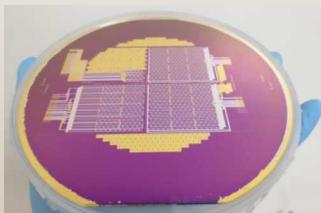
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- pathfinder technologies
  - microsystem-enabled photovoltaics
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## Outlook and Summary

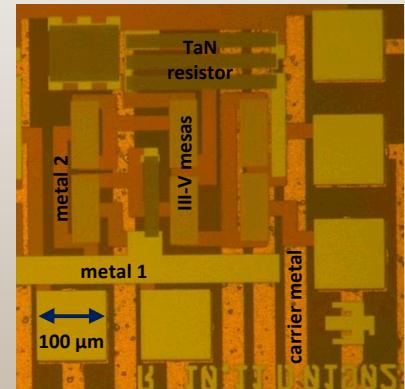
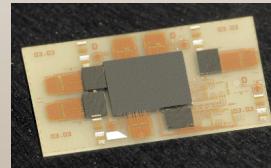
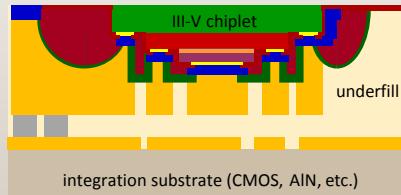
# Pathfinder Technologies

## Microsystem-Enabled Photovoltaics



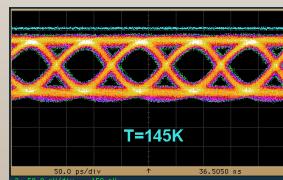
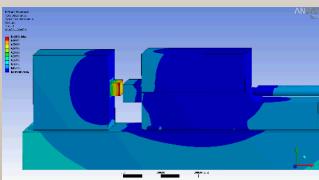
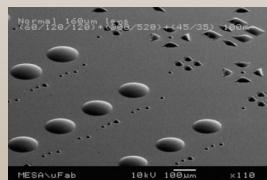
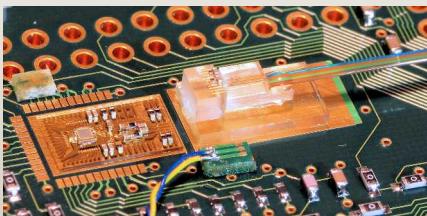
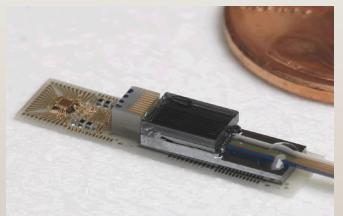
- wafer-level oxide bonding for multi-junction solar cells
- InGaAsP/InP and InGaP/GaAs devices on silicon
- dielectric interfaces with III-V substrate removal
- integration with collection optics

## Heterogeneous III-V/CMOS Microelectronics



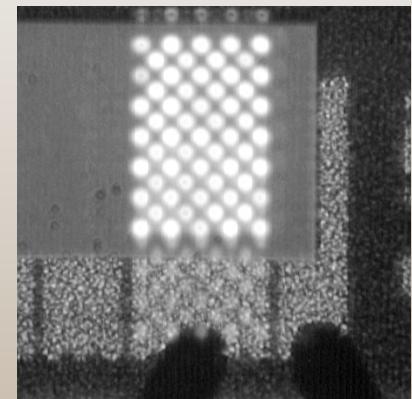
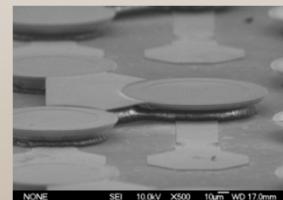
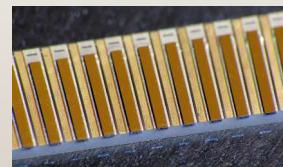
- complementary integration of GaAs and InP microelectronics
- III-V microelectronics circuitry on CMOS ASICs

## Extreme Environment Applications



- custom photonics, optics, electronics for cryogenic interconnects
- advanced optoelectronics and integration for radiation hardness

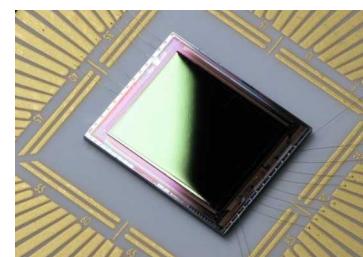
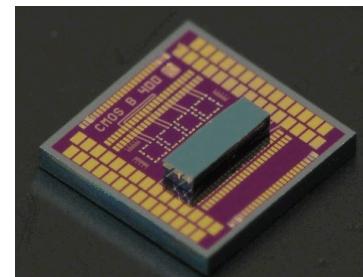
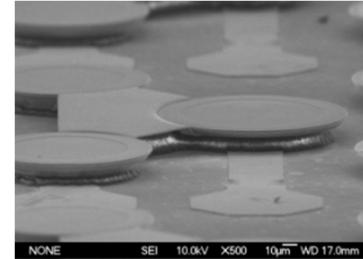
## High Performance Photonics



- high-power edge & surface emitters on AlN and diamond
- RF packaging for high-speed test and measurement

# Summary

- Heterogeneous integration of III-V photonics
  - provides high performance and more-than-Moore functionality
  - “best” approach depends on the application
    - package and wirebond, flip-chip, wafer-scale oxide bonding, DBI, ...
- Optical microsystem integration
  - leveraging extensive III-V capabilities
  - trusted microelectronics design/fabrication
  - heterogeneous integration as part of the fabrication process
- Numerous applications at Sandia
  - advanced FPAs (infrared/vis/UV/x-ray)
  - microscale optical sensors
  - optical communications for HPC and satellites
  - high power lasers
  - telecommunications
  - photovoltaics



# Acknowledgements

- Technical development / systems & applications:

Kent Geib

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Mark Overberg

Jin Kim

Jeffrey Cederberg

Thomas Gurrieri

Alejandro Griñé

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Para Parameswaran

Victoria Sanchez

Melissa Cavaliere

Samuel Hawkins

Christopher Nordquist

Anna Tauke-Pedretti

Carlos Sanchez

Allen Vawter

Charles Sullivan

- Funding sources:

Sandia LDRD

Department of Defense (DARPA, NSA, Army, ARDEC, AMRDEC)

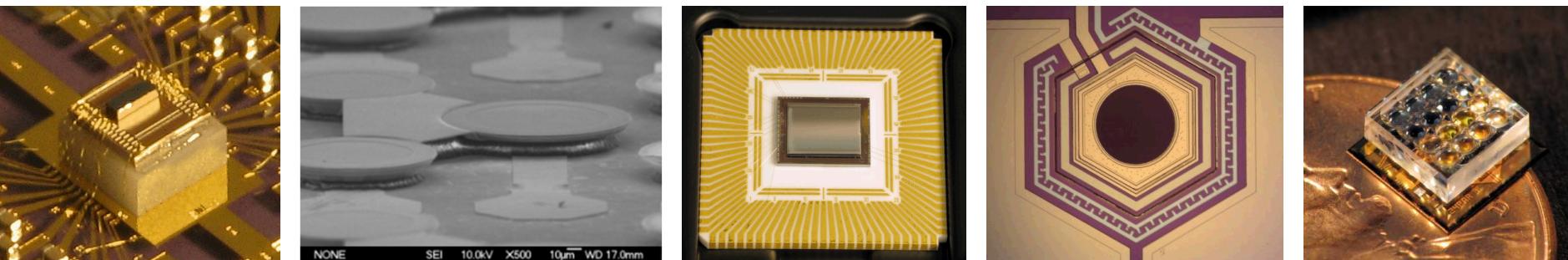
Department of Energy (NNSA, ARPA-E)



Sandia  
National  
Laboratories



*Exceptional service in the national interest*



## Heterogeneous Integration of III-V Photonics and Silicon Electronics for Advanced Optical Microsystems

Gordon A. Keeler, Kent M. Geib, Darwin K. Serkland, Gregory M. Peake, Mark E. Overberg,  
Jeffrey G. Cederberg, Thomas M. Gurrieri, Jin K. Kim, and Charles T. Sullivan

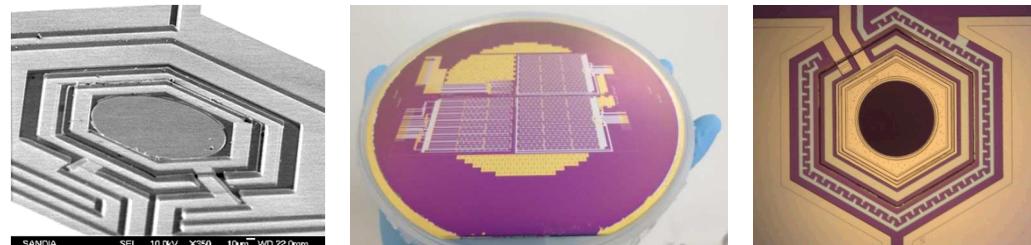
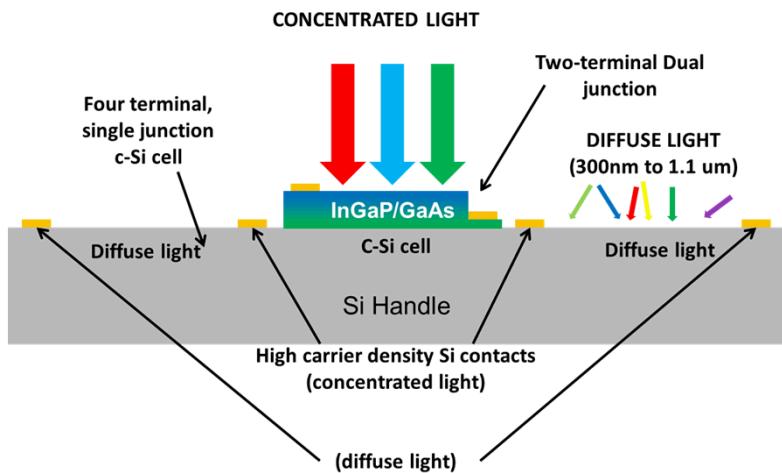
### Additional Slides



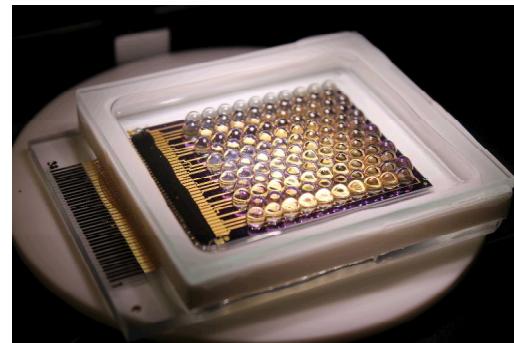
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# Microsystem-Enabled Photovoltaics (MEPV)

- Wafer-level bonding for microscale multi-junction solar cells
  - InGaAsP/InP and InGaP/GaAs devices on silicon
- Dielectric interfaces with III-V substrate removal
  - re-use of substrates to reduce ultimate cost
- Photonic microsystem prototyping
  - integration with collection optics



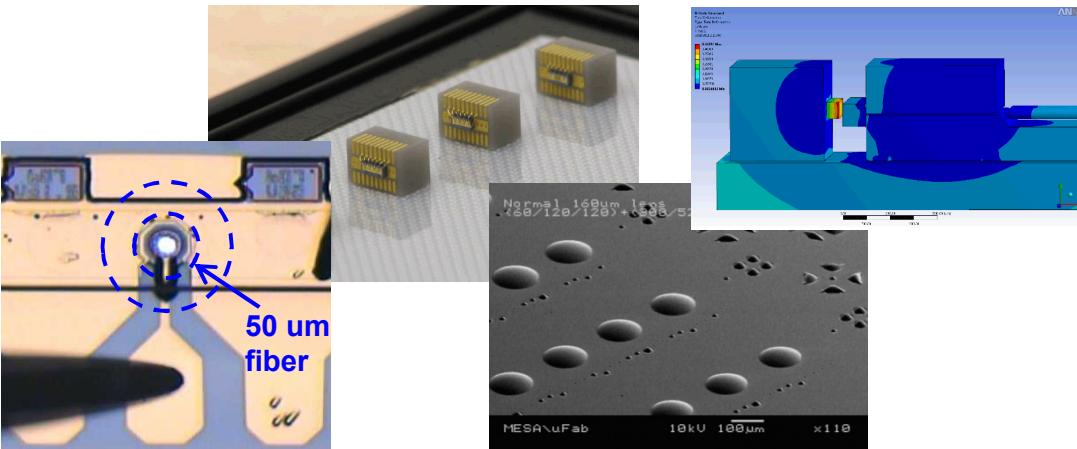
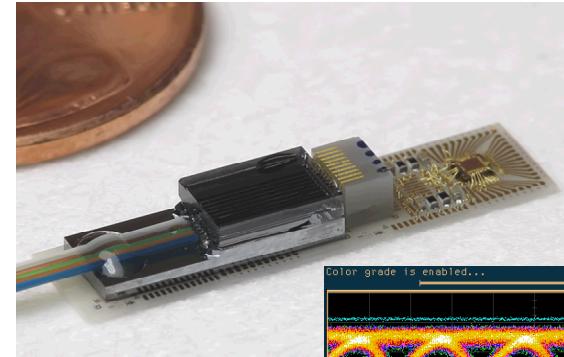
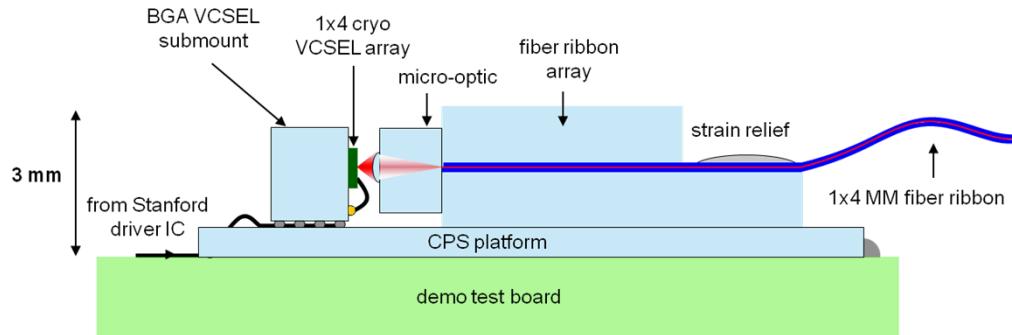
wafer-level integration of III-V and silicon cells



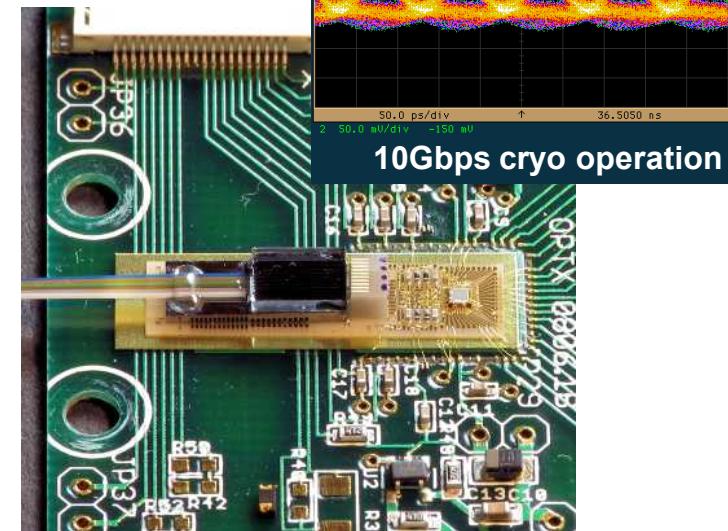
MEPV packaged module

# Cryogenic Optical Transceivers

- Integration of custom low-power cryogenic VCSELs, custom CMOS driver IC, passives, microlenses, and optical fiber array for satellite communications



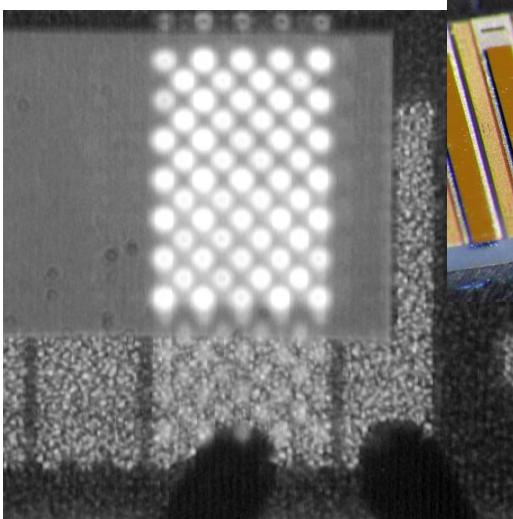
microfabrication, modeling, and assembly of transceiver elements



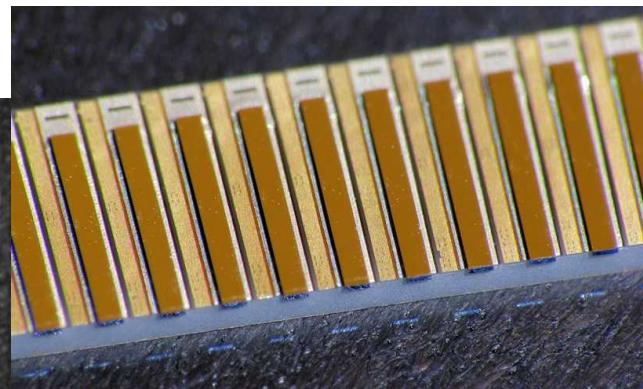
prototype assembled for cryo testing with FPA

# High-Power Laser Arrays

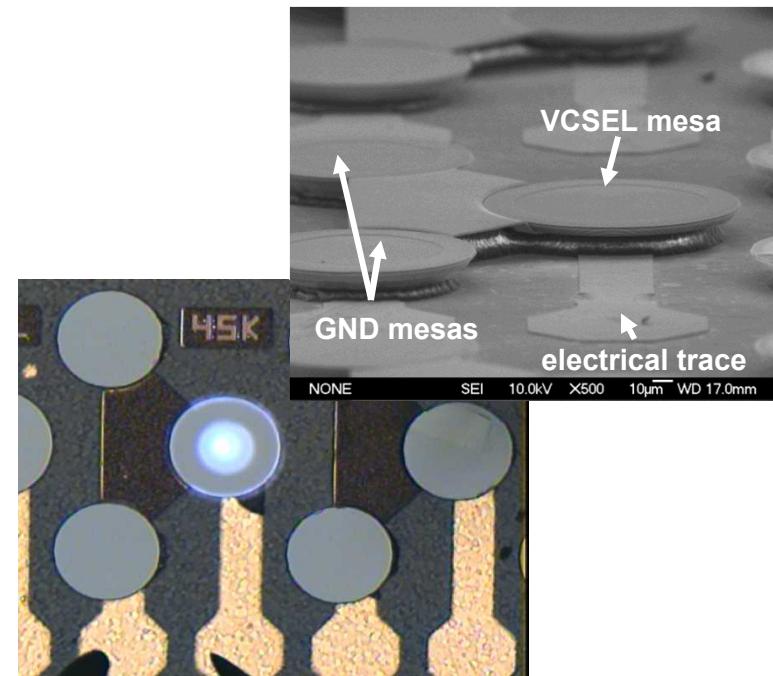
- Multiple programs have require custom high-power laser arrays
  - integration enables high density & efficient coupling to AlN heatsinks
- Various approaches exploited
  - serial attachment of discrete devices with AuSn solder
  - high-density 980nm VCSEL arrays with In solder
  - 850nm VECSELs with substrate removal for reduced optical absorption



10W VCSEL array



high-power laser bars on heatsink



high-power 850nm VCSELs on AlN